

SESSION 4

14.00-17.00

-WEDNESDAY, AUGUST 30

International Congress Hall

Ion Implantation & Device Technology (II)

Chairman

S. Namba

Osaka University

Toyonaka, Osaka

T. Tokuyama

Hitachi Ltd.

Kokubunji, Tokyo

Organizer

M. Tsurushima

Electrotechnical Laboratory

Tanashi, Tokyo

H. Ohmura

Tokyo Shibaura Electric Co.,
Ltd.

Kawasaki, Kanagawa

